

METHOD AND APPARATUS FOR SELECTIVELY ALTERING DIELECTRIC PROPERTIES OF LOCALIZED SEMICONDUCTOR DEVICE REGIONS

Abstract

A method for selectively altering dielectric properties of a semiconductor device. In an exemplary embodiment, the method includes applying energy to a local region of interest, the local region of interest including a thermally alterable dielectric such that said heating caused by the applied energy causes a dielectric constant of the thermally alterable dielectric to change.